

ABSTRACT OF THE DISCLOSURE

A pattern and method for forming a pattern includes providing a substrate on which a plurality of unit panels and etching object layers on the respective unit panel areas are formed, dividing the substrate into at least two or more areas, providing a cliché on which multiple grooves are formed, filling resist in the grooves, applying the resist filled in the groove of the cliché onto the etching object layer of the substrate by the divided area unit.